

Intrinsic defects and passivation mechanisms in Al₂O₃ ALD films

Karsten Henkel, Małgorzata Kot, Dieter Schmeißer

*Brandenburg University of Technology Cottbus-Senftenberg, Applied Physics and Sensor Technology,
K.-Wachsmann-Allee 17, 03046 Cottbus, Germany*

The characterization of intrinsic defect mechanisms in Al₂O₃ thin films is essential for their effective use in surface passivation schemes for solar cells. Particularly, perovskite solar cells (PSC) have shown an enhanced long-term stability and an improved protection against ambient conditions when an ALD-Al₂O₃ layer is introduced into the PSC stack [1].

In this work, we discuss comparatively ALD-Al₂O₃ films prepared on different substrates (including MAPI: CH₃NH₃PbI₃) and by different process parameters (thermal-ALD, plasma-enhanced-ALD, substrate temperature). These films were analyzed by resonant photoelectron spectroscopy.

Intrinsic defect states within the electronic band gap were observed including excitonic, polaronic, and charge-transfer defect states, where their relative abundance depends on the choice of the used ALD parameters and substrate [2,3]. The most pronounced signature of excitonic states is found for the Al₂O₃ film prepared on MAPI at room temperature. It points to a strong distortion of the octahedral coordinated network with a high number of tetrahedral sites which have a high affinity for OH adsorption and, hence, are responsible for perovskite protection against humidity [2].

- [1] M. Kot et al., ChemSusChem 9 (2016) 3401.
- [2] K. Henkel, M. Kot, D. Schmeißer, J. Vac. Sci. Technol. A 35 (2017) 01B125.
- [3] K. Henkel, M. Kot, M. Richter, M. Tallarida, D. Schmeißer, in K. Wandelt (Ed.): Encyclopedia of Interfacial Chemistry: Surface Science and Electrochemistry, Elsevier, Oxford, 2018, vol. 3.1, pp 18-26.